

Fuliang Wang

List of Publications by Year in descending order

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papers

645
citations

567281

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times ranked

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citing authors

#	ARTICLE	IF	CITATIONS
1	Dispensing of high concentration Ag nano-particles ink for ultra-low resistivity paper-based writing electronics. <i>Scientific Reports</i> , 2016, 6, 21398.	3.3	43
2	Effect of Ultrasound on Copper Filling of High Aspect Ratio Through-Silicon Via (TSV). <i>Journal of the Electrochemical Society</i> , 2017, 164, D126-D129.	2.9	31
3	Parameters Analysis of TSV Filling Models of Distinct Chemical Behaviours of Additives. <i>Electrochimica Acta</i> , 2016, 221, 70-79.	5.2	30
4	Ultrasonic Vibration at Thermosonic Flip-Chip Bonding Interface. <i>IEEE Transactions on Components, Packaging and Manufacturing Technology</i> , 2011, 1, 852-858.	2.5	29
5	Stress-induced atom diffusion at thermosonic flip chip bonding interface. <i>Sensors and Actuators A: Physical</i> , 2009, 149, 100-105.	4.1	28
6	Numerical modeling and experimental verification of copper electrodeposition for through silicon via (TSV) with additives. <i>Microelectronic Engineering</i> , 2017, 170, 54-58.	2.4	27
7	High-speed and high-quality TSV filling with the direct ultrasonic agitation for copper electrodeposition. <i>Microelectronic Engineering</i> , 2017, 180, 30-34.	2.4	27
8	Dynamic through-silicon-via filling process using copper electrochemical deposition at different current densities. <i>Scientific Reports</i> , 2017, 7, 46639.	3.3	21
9	Effects of applied potential and the initial gap between electrodes on localized electrochemical deposition of micrometer copper columns. <i>Scientific Reports</i> , 2016, 6, 26270.	3.3	20
10	Ultrasonic-Assisted Sintering of Silver Nanoparticles for Flexible Electronics. <i>Journal of Physical Chemistry C</i> , 2017, 121, 28515-28519.	3.1	20
11	Parametric Electrochemical Deposition of Controllable Morphology of Copper Micro-Columns. <i>Journal of the Electrochemical Society</i> , 2016, 163, E322-E327.	2.9	18
12	Modeling and Experimental Study of the Kink Formation Process in Wire Bonding. <i>IEEE Transactions on Semiconductor Manufacturing</i> , 2014, 27, 51-59.	1.7	17
13	Experiment study of dynamic looping process for thermosonic wire bonding. <i>Microelectronics Reliability</i> , 2012, 52, 1105-1111.	1.7	16
14	Effect of Capillary Trace on Dynamic Loop Profile Evolution in Thermosonic Wire Bonding. <i>IEEE Transactions on Components, Packaging and Manufacturing Technology</i> , 2012, 2, 1550-1557.	2.5	15
15	Ultrasonic Effects in the Thermosonic Flip Chip Bonding Process. <i>IEEE Transactions on Components, Packaging and Manufacturing Technology</i> , 2013, 3, 336-341.	2.5	15
16	Ultrasound aided smooth dispensing for high viscoelastic epoxy in microelectronic packaging. <i>Ultrasonics Sonochemistry</i> , 2016, 28, 15-20.	8.2	15
17	Effect of molecular weight and concentration of polyethylene glycol on through-silicon via filling by copper. <i>Microelectronic Engineering</i> , 2019, 215, 111003.	2.4	15
18	Graphene/Glycerin Solution-Based Multifunctional Stretchable Strain Sensor with Ultra-High Stretchability, Stability, and Sensitivity. <i>Nanomaterials</i> , 2019, 9, 617.	4.1	15

#	ARTICLE	IF	CITATIONS
19	Experimental Study of Thermosonic Gold Bump Flip-Chip Bonding With a Smooth End Tool. IEEE Transactions on Components, Packaging and Manufacturing Technology, 2013, 3, 930-934.	2.5	14
20	Effect of Voltage and Gap on Micro-Nickel-Column Growth Patterns in Localized Electrochemical Deposition. Journal of the Electrochemical Society, 2017, 164, D297-D301.	2.9	14
21	Dynamics of filling process of through silicon via under the ultrasonic agitation on the electroplating solution. Microelectronic Engineering, 2017, 180, 25-29.	2.4	14
22	Dynamics of Free Air Ball Formation in Thermosonic Wire Bonding. IEEE Transactions on Components, Packaging and Manufacturing Technology, 2012, 2, 1389-1393.	2.5	12
23	Fabrication of Micro Copper Walls by Localized Electrochemical Deposition through the Layer by Layer Movement of a Micro Anode. Journal of the Electrochemical Society, 2017, 164, D758-D763.	2.9	12
24	Effect of cetyl-trimethyl-ammonium-bromide (CTAB) and bis (3-sulfopropyl) disulfide (SPS) on the through-silicon-via (TSV) copper filling. Microelectronic Engineering, 2019, 217, 111109.	2.4	11
25	The key role of suppressor diffusion in defect-free filling of the through-silicon-via with high depth. Journal of Micromechanics and Microengineering, 2019, 29, 055005.	2.6	11
26	Experiment and simulation of single inhibitor SH110 for void-free TSV copper filling. Scientific Reports, 2021, 11, 12108.	3.3	11
27	Fabrication of Micro-Sized Copper Columns Using Localized Electrochemical Deposition with a 20 μ m Diameter Micro Anode. ECS Journal of Solid State Science and Technology, 2019, 8, P223-P227.	1.8	10
28	Effect of Bis-(3-sulfopropyl) Disulfide and Chloride Ions on the Localized Electrochemical Deposition of Copper Microstructures. Journal of the Electrochemical Society, 2017, 164, D419-D424.	2.9	9
29	Stress-dislocation interaction mechanism in low-temperature thermo-compression sintering of Ag NPs. AIP Advances, 2018, 8, .	1.3	9
30	Design of Ultrasonic Generator Based on DDS and PLL Technology. , 2007, , .		7
31	Height Measurement of Micro-Solder Balls on Metal Pad by White Light Projection. IEEE Transactions on Components, Packaging and Manufacturing Technology, 2012, 2, 1545-1549.	2.5	6
32	Modeling of Deep Cavity Looping Process on 3-D Stacked Die Package. IEEE Transactions on Semiconductor Manufacturing, 2013, 26, 169-175.	1.7	6
33	Experimental and Modeling Studies of Looping Process for Wire Bonding. Journal of Electronic Packaging, Transactions of the ASME, 2013, 135, .	1.8	6
34	Parameter analysis on the ultrasonic TSV-filling process and electrochemical characters. Journal of Micromechanics and Microengineering, 2017, 27, 105003.	2.6	6
35	Effects of additives with different acids on the through-silicon vias copper filling. Microelectronic Engineering, 2018, 200, 51-55.	2.4	6
36	Interaction effect of suppressor concentration and current density on the copper deposition rate in TSV filling process. Microelectronic Engineering, 2019, 216, 111022.	2.4	6

#	ARTICLE	IF	CITATIONS
37	The Design and Realization of Machine Vision System in Flip - chip Bonder. , 2006, , .		5
38	Parameters determination for modelling of copper electrodeposition in through-silicon-via with additives. Microelectronic Engineering, 2018, 196, 25-31.	2.4	5
39	Experimental study of current density in copper filling process within deep through-silicon vias with high aspect ratio. Journal of Micromechanics and Microengineering, 2019, 29, 125013.	2.6	5
40	Thermo-compression bonding process characteristics and shape control of Cu-pillar microbump joints by optimizing of solder melting. Journal of Materials Science: Materials in Electronics, 2022, 33, 10471-10485.	2.2	5
41	Study of Complex Looping With Five Kinks in Thermosonic Wire Bonding by Using Variable-Length Link-Spring Model. IEEE Transactions on Components, Packaging and Manufacturing Technology, 2019, 9, 375-379.	2.5	4
42	Using a triblock copolymer as a single additive in high aspect ratio through silicon via (TSV) copper filling. Microelectronic Engineering, 2021, 244-246, 111554.	2.4	4
43	Long distance and direction-controllable conveyor for automatic particle transportation based on optical tweezers. Sensors and Actuators A: Physical, 2022, 333, 113223.	4.1	4
44	Fabrication of micro-sized-copper column array through localized electrochemical deposition using 20- μ m-diameter micro-anode. Journal of Solid State Electrochemistry, 2022, 26, 799-808.	2.5	4
45	High-Frequency and Low-Temperature Thermosonic Bonding of Lead-Free Microsolder Ball on Silver Pad Without Flux. Journal of Electronic Packaging, Transactions of the ASME, 2014, 136, .	1.8	3
46	Comparison of Fundamental Frequency and Sweep Resistance of Different Wire Loops Using Finite Element Model. International Journal of Structural Stability and Dynamics, 2015, 15, 1450032.	2.4	3
47	Development of an Ultralong Ultralow n-Loop for Wire Bonding. IEEE Transactions on Semiconductor Manufacturing, 2015, 28, 50-54.	1.7	3
48	A novel model for through-silicon via (TSV) filling process simulation considering three additives and current density effect. Journal of Micromechanics and Microengineering, 2017, 27, 125017.	2.6	3
49	Study on the effect of CNT on the improved mechanical performance of flexible Ag NPs/CNT based electronics. AIP Advances, 2019, 9, .	1.3	3
50	Effects of polyethyleneimine, applied potential and the initial gap on the localized electrochemical deposition of silver microcolumns. Microelectronic Engineering, 2021, 247, 111582.	2.4	3
51	An ultrasensitive bacteria biosensor using "multilayer cake" silver microelectrode based on local high electric field effect. Applied Physics Letters, 2022, 121, 013701.	3.3	3
52	Atom diffusion mechanism of thermo-sonic flip chip bonding interface. , 2007, , .		2
53	Finite element analysis of wire clamp for wire bonding. , 2012, , .		2
54	Variable-Length Link-Spring Model for Kink Formation During Wire Bonding. Journal of Electronic Packaging, Transactions of the ASME, 2013, 135, .	1.8	2

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55	Effect of aliphatic-amine ethoxy sulfonates (AESS) on micro copper columns fabrication by using localized electrochemical deposition. Materials Research Express, 2019, 6, 0965b3.	1.6	2
56	Void Free TSV Copper Filling using Single Additive 3-(1-Pyridinio)-1-Propanesulfonate (PPS). , 2020, , .		2
57	Dynamic current characteristic of ultrasonic transducer for wire bonding. , 2010, , .		1
58	Investigation of Complex Looping Process for Thermosonic Wire Bonding. IEEE Transactions on Semiconductor Manufacturing, 2014, 27, 238-245.	1.7	1
59	Growth pattern and morphology of micro nickel column by localized electrochemical deposition. , 2016, , .		1
60	Localized electrochemical deposition of micrometer copper columns as affected by adding sulfuric acid. , 2016, , .		1
61	Effect of ultrasound agitation on the properties of copper electrodeposition in micro-via. , 2018, , .		1
62	Effect of sulfuric acid concentration on the quality of copper microcolumns in localized electrochemical deposition. Materials Research Express, 2020, 7, 056515.	1.6	1
63	Study on the Chip and Tool Tip Vibration of Thermosonic Flip Chip Bonding. , 2007, , .		0
64	Effect of voltage and gap on the morphology of the Ni micro-column by localized electrochemical deposition. , 2016, , .		0
65	Mathematical simulation and experimental verification for through silicon via with additives. , 2018, , .		0
66	Co-deposition of Nano-Size SiC Particles in Micro-Via. , 2018, , .		0
67	Filling technique of through silicon via by co-depositing copper and SiC nano-particles. , 2020, , .		0
68	The Shape Control Process of a Cu/SnAg Solder Joint with a Ni insertion Using Thermo-Compression Bonding. , 2021, , .		0
69	Electroless Copper Deposition with Pyramidal Micro-cones Morphology for Low-temperature Cu-Cu Bump Interconnections. , 2021, , .		0